

TJK/408

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of)	ATOMIC LAYER DEPOSITION
)	METHOD AND SEMICONDUCTOR
Hwang et al.)	DEVICE FABRICATING
)	APPARATUS HAVING ROTATABLE
Application No.)	GAS INJECTORS
)	Group Art Unit:
Filing Date:)	
		Examiner:

Commissioner for Patents
P.O. Box 1450
Mail Stop: Divisional Patent Application
Alexandria, VA 22313-1450

Amendment to the Specification:

--CROSS REFERENCE TO RELATED APPLICATION

This application is a Divisional of U.S. patent application serial No. 09/927,004 entitled
“ATOMIC LAYER DEPOSITION METHOD AND SEMICONDUCTOR DEVICE
FABRICATING APPARATUS HAVING ROTATABLE GAS INJECTORS”, filed on August
8, 2001 which claims the priority of Korean patent application serial No. 2000-46216, filed
August 9, 2000.--